

Appl. No. : 10/561,802
Filed : December 22, 2005

ABSTRACT

Amendment please enter
Ho Van Le
08/10/10 A developer composition for resists which has a high dissolution rate (high developing sensitivity). The developer composition for resists comprises an organic quaternary ammonium base as a main component and a surfactant containing an anionic surfactant represented by formula (I).

HOA VAN LE
PRIMARY EXAMINER

9492496
081010